

Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application:

1           1.       (currently amended) A device for holding a nanolithography template used for  
2       imprinting a nanolithography pattern on a substrate, said device comprising:  
3           a body having an opening to receive said nanolithography template, said body for  
4       positioning said template relative to said substrate for imprinting said nanolithography pattern on  
5       said substrate; and  
6           a supporting plate coupled to said body and positioned relative to said nanolithography  
7       template to support a force of said imprinting on said nanolithography template, with said  
8       supporting plate being substantially transparent to a curing agent.

1           2.       (original) The device as recited in claim 1 wherein said curing agent comprises  
2       ultraviolet radiation.

1           3.       (original) The device as recited in claim 1 wherein said supporting plate is formed  
2       from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

1           4.       (currently amended) The device as recited in claim 1 further including a vacuum  
2       system in fluid communication with said supporting plate to apply a vacuum to said  
3       nanolithography template.

1           5.       (original) The device as recited in claim 1 further including a vacuum system in  
2       fluid communication with said supporting plate to apply a vacuum between said supporting plate  
3       and said body.

1           6.       (currently amended) The device as recited in claim 1 wherein said supporting  
2 plate is configured to reduce deformation of said nanolithography template due to forces present  
3 during an imprint lithography process.

1           7.       (original) The device as recited in claim 1 further including a reflective element  
2 connected to a portion of said body located within said opening.

1           8.       (currently amended) A device for holding a nanolithography template used for  
2 imprinting a nanolithography pattern on a substrate, said device comprising:  
3           a body having an opening to receive said nanolithography template, said body for  
4 positioning said template relative to said substrate for for imprinting said nanolithography pattern  
5 on said substrate; and  
6           a supporting plate coupled to said body and positioned relative to said nanolithography  
7 template to support a force of said imprinting on said nanolithography template, with said  
8 supporting plate substantially transparent to ultraviolet radiation.

1           9.       (original) The device as recited in claim 8 wherein said supporting plate is formed  
2 from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

1           10.      (currently amended) The device as recited in claim ~~[[181]]~~ 8 further including a  
2 vacuum system in fluid communication with said supporting plate to apply a vacuum to said  
3 nanolithography template.

1           11.      (original) The device as recited in claim 8 further including a vacuum system in  
2 fluid communication with said supporting plate to apply a vacuum between said supporting plate  
3 and said body.

1           12.      (currently amended) The device as recited in claim 8 wherein said supporting  
2 plate is configured to reduce deformation of said nanolithography template due to forces present  
3 during an imprint lithography process.

1           13.     (original) The device as recited in claim 8 further including a reflective element  
2 connected to a portion of said body located within said opening.

1           14.     (currently amended) A device for holding a nanolithography template used for  
2 imprinting a nanolithography pattern on a substrate, said device comprising:  
3           a body having an opening to receive said nanolithography template, said body for  
4 positioning said template relative to said substrate for imprinting said nanolithography pattern on  
5 said substrate;  
6           a supporting plate coupled to said body and positioned relative to said nanolithography  
7 template to support a force of said imprinting on said nanolithography template, with said  
8 supporting plate substantially transparent to a curing agent; and  
9           a vacuum system in fluid communication with said supporting plate to apply a vacuum  
10 between said supporting plate and said body.

1           15.     (original) The device as recited in claim 14 wherein said curing agent comprises  
2 ultraviolet radiation.

1           16.     (original) The device as recited in claim 14 wherein said supporting plate is  
2 formed from material selected from a set of materials consisting of quartz, sapphire, and silicon  
3 dioxide.

1           17.     (currently amended) The device as recited in claim 14 wherein said supporting  
2 plate is configured to reduce deformation of said nanolithography template due to forces present  
3 during an imprint lithography process.

1           18.     (original) The device as recited in claim 14 further including a reflective element  
2 connected to a portion of said body located within said opening.